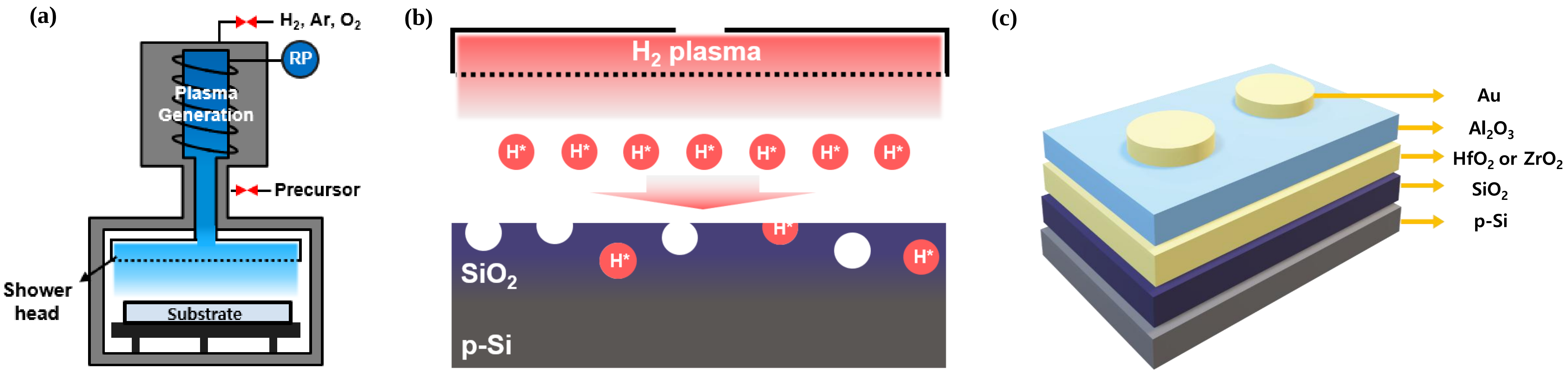

Fig 1. Schematic Diagrams of (a) the ALD and HPT in-situ process chamber, (b) HPT effect, and (c) CTM devices studied in this study.

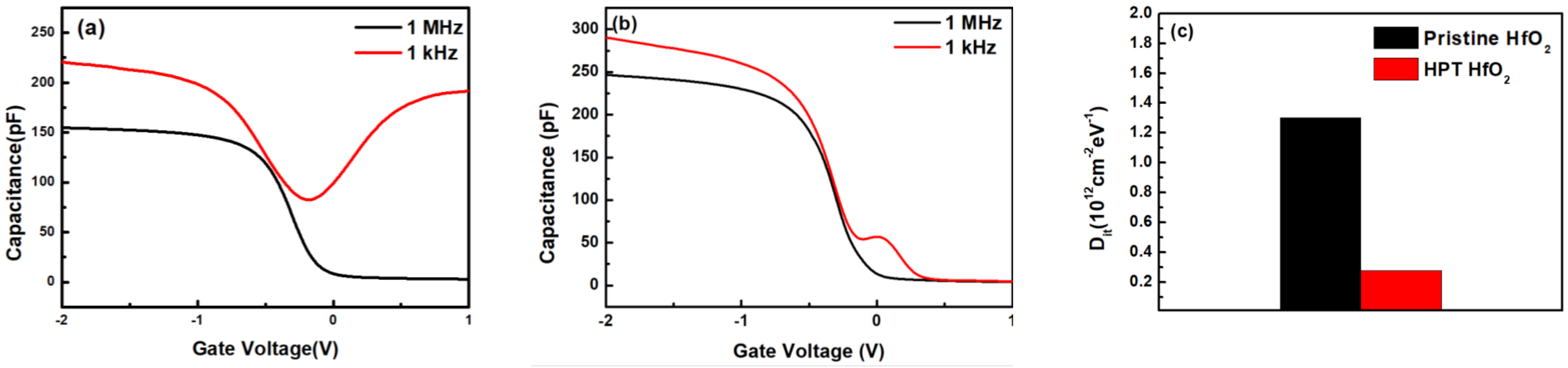

Fig 2. C-V characteristics of (a) pristine and (b) HPT HfO_2 films. (c) Comparision of D_{it} for the HfO_2 films by using Castagné–Vapaille method.